

### Amendments to the Specification

Please replace col. 3, lines 54-63 with the following rewritten paragraph:

FIG. 1 shows a radiation source indicated by reference number 1, and a filter which is generally indicated by reference number 2. The processing organ that is used in the apparatus for, for example, extreme ultraviolet lithography, is [not] shown as PO. This processing organ is located at the side of the filter 2 facing away from the radiation source 1. The filter 2 comprises a number of plates 3 positioned in a radial direction from the radiation source 1. It is possible to position said plates in a honeycomb construction, or as a plurality of concentric cones as shown in FIG. 3.